



TSMC-02-345

December 15, 2003

To: Commissioner for Patents
P.O.Box 1450
Alexandria, VA 22313-1450

Fr: George O. Saile, Reg. No. 19,572
28 Davis Avenue
Poughkeepsie, N.Y. 12603

Subject: | Serial No. 10/672,410 09/26/03 |
Li-Te S. Lin et al.
A TEST STRUCTURE FOR DIFFERENTIATING
THE LINE AND VIA CONTRIBUTION IN
STRESS MIGRATION
| _____ |

INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation
In An Application.

The following Patents and/or Publications are submitted to
comply with the duty of disclosure under CFR 1.97-1.99 and
37 CFR 1.56.

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being
deposited with the United States Postal Service as first class
mail in an envelope addressed to: Commissioner for Patents,
P.O. Box 1450, Alexandria, VA 22313-1450, on December 19, 2003.

Stephen B. Ackerman, Reg.# 37761

Signature/Date

 12/19/03

TSMC-02-345

U.S. Patent 6,342,733 to Hu et al., "Reduced Electro-migration and Stressed Induced Migration of Cu Wires by Surface Coating," describes a test structure for EM and SM.

U.S. Patent 6,004,827 to Ryan, "Integrated Circuit Processing," describes various test structures with aluminum runners and overlying dielectrics.

U.S. Patent 5,930,587 to Ryan, "Stress Migration Evaluation Method," describes an SM method and test structure.

Sincerely,

A handwritten signature in black ink, appearing to read 'SBA', with a long horizontal flourish extending to the right.

Stephen B. Ackerman,
Reg. No. 37761

FD-302 (Rev. 1-25-60) PTO-1449

DEC 24 2003

INFORMATION DISCLOSURE CITATION IN AN APPLICATION

(Use several sheets if necessary)

Doctel Number (Optional)

TSMC-02-345

Application Number

10/672,410

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Applicants Li-te S. Lin et al.

Filing Date

Filing Date 09/26/03

Group Art Unit

U. S. PATENT DOCUMENTS

[illegible]

FOREIGN PATENT DOCUMENTS

[illegible]

OTHER DOCUMENTS (Including Author, Title, Date, Portion of Pages, Etc.)

EXAMINEE

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.